

Addition/Correction

Solvent Resistant Photocurable “Liquid Teflon” for Microfluidic Device Fabrication [J. Am. Chem. Soc. 2004, 126, 2322–2323].

Jason P. Rolland, R. Michael Van Dam, Derek A. Schorzman, Stephen R. Quake, and Joseph M. DeSimone

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Solvent Resistant Photocurable “Liquid Teflon” for Microfluidic Device Fabrication [*J. Am. Chem. Soc.* **2004**, *126*, 2322–2323]. Jason P. Rolland, R. Michael Van Dam, Derek A. Schorzman, Stephen R. Quake,* and Joseph M. DeSimone*

Page 2322. The authors wish to change the title from “Solvent Resistant Photocurable ‘Liquid Teflon’ for Microfluidic Device Fabrication” to “Solvent Resistant Photocurable Liquid Fluoropolymers for Microfluidic Device Fabrication”.

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